Advances in Anodic Alumina MCP development

Gleb Drobycheva, Andrei Barysevicha, Kirill Delendikb, Patrick Nédélec, Daniel Sillouc, Olga Voitikb

aInstitute for Nuclear Problems, 11, Bobruiskaya Str., Minsk, 220050, Belarus
bInstitute of Physics, 22, Logojsky trakt., Minsk, 220090, Belarus
cLaboratory d’Annecy-le-Vieux de Physique des Particules, 9, Chemin de Bellevue, F-74941, Annecy-le-Vieux, France
Main results

- A technology to increase electric conductivity of AAO was developed. New samples have resistance around tens of MOhm. The resistivity can be varied in wide region depends on the technological production parameters.

- An etching technology, which has a characteristic “anisotropy” due to porous structure of the AAO is also developed. Produced channels are open-ended and have constant diameter along the full depth of a plate. However, a technology optimization is still required. We plan to reach 150-180 µm of MCP thickness with conserving of the MCP structure parameters.